

WE CLAIM:

- 1 1. A liquid crystal display with a large pixel
2 aperture ratio comprising:
3 a liquid crystal layer sandwiched between first
4 and second substrates;
5 an array of thin film transistors and
6 corresponding pixel electrodes mounted on said first
7 substrate, each of said thin film transistors including a
8 semiconductor layer, a gate electrode connected to a gate
9 address line, a drain electrode connected to a drain
10 address line, and a source electrode connected to one of
11 said corresponding pixel electrodes, and wherein said
12 pixel electrode connected to said source electrode
13 overlaps said gate and drain address lines along
14 longitudinal edges thereof; and
15 a substantially continuous insulating layer
16 having a dielectric constant ϵ no greater than about 3.0
17 disposed between said pixel electrode and said address
18 lines in sufficient thickness so as to reduce capacitive
19 cross-talk in the display by reducing the pixel
20 electrode-address line parasitic capacitance C_{pl} in the
21 areas of overlap.

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1 7. The liquid crystal display of claim 1, wherein
2 said pixel electrode overlaps said gate and drain address
3 lines along substantially their entire lengths so as to
4 increase the pixel aperture ratio of the display.

1 8. The liquid crystal display of claim 1, wherein
2 at least one via is defined for each pixel in said
3 insulating layer so that said pixel electrode can be
4 electrically connected to said source electrode through
5 said via.

1 9. The liquid crystal display of claim 8, wherein
2 said insulating layer defines another via for each pixel
3 so that said pixel electrode can also be connected to a
4 storage capacitor electrode through said another via.

1 10. The liquid crystal display of claim 1, wherein
2 said insulating layer includes Benzocyclobutene (BCB) and
3 has a dielectric constant ϵ of about 2.7 or less.

1 11. The liquid crystal display of claim 1, wherein
2 said pixel electrode overlaps said address lines along
3 their lengths by at least about 0.5 μm .

1 12. The liquid crystal display of claim 1, wherein
2 said semiconductor layer is intrinsic amorphous silicon
3 and is disposed between (i) said gate electrode and (ii)
4 said source and drain electrodes.

1 13. The liquid crystal display of claim 12, wherein
2 said pixel electrode is ITO and said drain electrode is
3 Mo.

1 14. A thin film transistor (TFT) structure
2 comprising:
3 a substantially transparent substrate;
4 a gate electrode located on said substrate and
5 adapted to be connected to a first address line;
6 a semiconductor layer located on said substrate
7 over said gate electrode;
8 a drain electrode located on said substrate
9 over said semiconductor layer and adapted to be connected
10 to a second address line;
11 a source electrode located on said substrate
12 over said semiconductor layer and spaced from said drain
13 electrode so as to define a transistor channel, said
14 source electrode adapted to be electrically connected to
15 a pixel electrode;
16 an insulating layer located on said substrate
17 over said source and drain electrodes, said insulating
18 layer being of sufficient thickness "d" and having a

19 sufficiently low dielectric constant value ϵ so that when
20 said pixel electrode overlaps one of said first and
21 second address lines, the resulting pixel electrode-
22 address line parasitic capacitance C_{pl} is sufficiently low
23 so as to substantially eliminate cross-talk.

1 15. The TFT structure of claim 14, wherein said
2 insulating layer is at least about 1.5 μm thick in areas
3 where the pixel electrode overlaps one of said address
4 lines.

1 16. The TFT structure of claim 14, wherein said
2 insulating layer includes Benzocyclobutene (BCB) and has
3 a dielectric constant ϵ of less than about 3.0.

1 17. The TFT structure of claim 14, wherein said
2 insulating layer has a dielectric constant of less than
3 about 3.0, a thickness of at least about 1.5 μm in the
4 overlap areas, and C_{pl} is no greater than about 0.01 pF.

1 18. A method of making a liquid crystal display
2 including an array of TFTs, the method comprising the
3 steps of:

4 providing a substantially transparent first
5 substrate;

6 disposing a gate metal layer on said first
7 substrate and patterning an array of TFT gate electrodes
8 and gate address lines therefrom;

9 disposing a semiconductor layer on said first
10 substrate over said gate electrodes and patterning the
11 semiconductor layer to form TFT areas;

12 disposing and patterning drain and source
13 electrodes on said substrate over the semiconductor
14 layer;

15 providing drain address lines for addressing
16 the drain electrodes;

17 disposing a substantially continuous organic
18 insulating layer on said substrate over said address
19 lines and said drain and source electrodes to a thickness
20 of at least about 1.5 μm ; and

21 disposing and patterning an array of
22 substantially transparent pixel electrodes on said
23 substrate over said insulating layer so that the
24 patterned pixel electrodes overlap at least one of said
25 gate and drain lines in order to increase the display's
26 pixel aperture ratio.

1 19. The method of claim 18, further comprising the
2 step of making the display so that the resulting pixel
3 electrode-address line parasitic capacitance C_{PL} defined
4 in the overlap areas is no greater than about 0.01 pF
5 when the pixel pitch of the display is about 150 μm .

1 20. The method of claim 18, wherein the insulating
2 layer is made substantially of Benzocyclobutene (BCB) and
3 has a dielectric constant ϵ less than about 3.0.

1 21. A liquid crystal display comprising:
2 a liquid crystal layer;
3 a substantially transparent substrate adjacent
4 said liquid crystal layer;
5 an array of thin film transistors disposed on
6 said substrate, said thin film transistors connected to
7 address lines and acting as switching elements for
8 energizing corresponding pixel electrodes;
9 a substantially transparent planarization layer
10 disposed on said array of transistors, said planarization
11 layer being located between (i) said pixel electrodes;
12 and (ii) said address lines; and
13 wherein said planarization layer includes
14 Benzocyclobutene (BCB) and has a dielectric constant of
15 less than/about 3.0.

1 22. The display of claim 21, wherein said pixel
2 electrodes overlap at least some of said address lines in
3 order to increase the pixel aperture ratio of the
4 display, and said planarization layer is at least about
5 1.5 μm thick in the areas of overlap so as to minimize
6 the parasitic capacitance created in the overlap areas
7 between the pixel electrodes and the address lines.

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